

Priority # 7

Access DB# 137281

SEARCH REQUEST FORM

Scientific and Technical Information Center

Requester's Full Name: Sin J. Lee Examiner #: 76060 Date: 11-4-04
Art Unit: 1752 Phone Number 301-2-1333 Serial Number: 101784, 806
Mail Box and Bldg/Room Location: 9D66 Results Format Preferred (circle): PAPER DISK E-MAIL

If more than one search is submitted, please prioritize searches in order of need.

Please provide a detailed statement of the search topic, and describe as specifically as possible the subject matter to be searched. Include the elected species or structures, keywords, synonyms, acronyms, and registry numbers, and combine with the concept or utility of the invention. Define any terms that may have a special meaning. Give examples or relevant citations, authors, etc, if known. Please attach a copy of the cover sheet, pertinent claims, and abstract.

Title of Invention: Please see attached Bib

Inventors (please provide full names): _____

Earliest Priority Filing Date: _____

For Sequence Searches Only Please include all pertinent information (parent, child, divisional, or issued patent numbers) along with the appropriate serial number.

Please ~~see~~ Search for
the alcoholic compd. of
Claim #3.
and/or the method of
reacting that compd.
to get the monomer of
Claim 1 or
to get the monomer
of claim #2.

STAFF USE ONLY

	Type of Search	Vendors and cost where applicable
Searcher: <u>K. Fisher</u>	NA Sequence (#) <u>76060</u>	STN _____
Searcher Phone #: _____	AA Sequence (#) _____	Dialog _____
Searcher Location: _____	Structure (#) <u>1</u>	Questel/Orbit _____
Date Searcher Picked Up: _____	Bibliographic _____	Dr. Link _____
Date Completed: <u>11/15/04</u>	Litigation _____	Lexis/Nexis _____
Searcher Prep & Review Time: <u>20</u>	Fulltext _____	Sequence Systems _____
Clerical Prep Time: _____	Patent Family _____	WWW/Internet _____
Online Time: <u>20</u>	Other _____	Other (specify) _____

Priority #7

Access DB# 137283

SEARCH REQUEST FORM

Scientific and Technical Information Center

Requester's Full Name: Sin J. Lee Examiner #: 76060 Date: 11-4-04
 Art Unit: 1752 Phone Number 301 2-1333 Serial Number: 101784, 806
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 Please provide a detailed statement of the search topic, and describe as specifically as possible the subject matter to be searched. Include the elected species or structures, keywords, synonyms, acronyms, and registry numbers, and combine with the concept or utility of the invention. Define any terms that may have a special meaning. Give examples or relevant citations, authors, etc, if known. Please attach a copy of the cover sheet, pertinent claims, and abstract.

Title of Invention: Please see attached Bib.

Inventors (please provide full names): _____

Earliest Priority Filing Date: _____

For Sequence Searches Only Please include all pertinent information (parent, child, divisional, or issued patent numbers) along with the appropriate serial number.

Please search for the
monomer of claim #2

and/or the polymer of claim #10

↓
 which is made from
 the monomer of
 cl. #2.

STAFF USE ONLY

Searcher: <u>K. Fuller</u>	Type of Search	Vendors and cost where applicable
Searcher Phone #: _____	NA Sequence (#): _____	STN <u>17</u>
Searcher Location: _____	AA Sequence (#) _____	Dialog _____
Date Searcher Picked Up: _____	Structure (#) <u>1</u>	Questel/Orbit _____
Date Completed: <u>11/15/04</u>	Bibliographic _____	Dr.Link _____
Searcher Prep & Review Time: <u>20</u>	Litigation _____	Lexis/Nexis _____
Clerical Prep Time: _____	Fulltext _____	Sequence Systems _____
Online Time: <u>20</u>	Patent Family _____	WWW/Internet _____
	Other _____	Other (specify) _____

priority # 7

Access DB# 137285

SEARCH REQUEST FORM

Scientific and Technical Information Center

Requester's Full Name: Sin J. Lee Examiner #: 76060 Date: 11-4-04
Art Unit: 1752 Phone Number 302-1333 Serial Number: 101784, 806
Mail Box and Bldg/Room Location: 9D66 Results Format Preferred (circle): PAPER DISK E-MAIL

If more than one search is submitted, please prioritize searches in order of need.

Please provide a detailed statement of the search topic, and describe as specifically as possible the subject matter to be searched. Include the elected species or structures, keywords, synonyms, acronyms, and registry numbers, and combine with the concept or utility of the invention. Define any terms that may have a special meaning. Give examples or relevant citations, authors, etc, if known. Please attach a copy of the cover sheet, pertinent claims, and abstract.

Title of Invention: Please see attached B.I.B

Inventors (please provide full names): _____

Earliest Priority Filing Date: _____

**For Sequence Searches Only* Please include all pertinent information (parent, child, divisional, or issued patent numbers) along with the appropriate serial number.*

Please search for the

monomer
of claim #1

and/or

the

polymer
of claim # 6

which is made
from the monomer
of claim # 1

STAFF USE ONLY

Searcher: <u>K. Fuller</u>	Type of Search	Vendors and cost where applicable
Searcher Phone #: _____	NA Sequence (#) _____	STN _____
Searcher Location: _____	AA Sequence (#) _____	Dialog _____
Date Searcher Picked Up: _____	Structure (#) <u>1</u>	Questel/Orbit _____
Date Completed: <u>11/15/04</u>	Bibliographic _____	Dr.Link _____
Searcher Prep. & Review Time: <u>20</u>	Litigation _____	Lexis/Nexis _____
Clerical Prep Time: _____	Fulltext _____	Sequence Systems _____
Online Time: <u>20</u>	Patent Family _____	WWW/Internet _____
	Other _____	Other (specify) _____



STIC Search Report

EIC 1700

STIC Database Tracking Number: 137281

TO: Sin J Lee
Location: Rem 9D60
Art Unit : 1752
November 15, 2004

Case Serial Number: 10/784806

From: Kathleen Fuller
Location: EIC 1700
REMSEN 4B28
Phone: 571/272-2505
Kathleen.Fuller@uspto.gov

Search Notes

This search covers all three requested searches for the claims 1,2 and 3., There were only 6 structures and only one CA reference to the applicants.



STIC Search Results Feedback Form

EIC17000

Questions about the scope or the results of the search? Contact *the EIC searcher* or contact:

Kathleen Fuller, EIC 1700 Team Leader
571/272-2505 REMSEN 4B28

Voluntary Results Feedback Form

- I am an examiner in Workgroup: Example: 1713
➤ Relevant prior art **found**, search results used as follows:

- ☐ 102 rejection
- ☐ 103 rejection
- ☐ Cited as being of interest.
- ☐ Helped examiner better understand the invention.
- ☐ Helped examiner better understand the state of the art in their technology.

Types of relevant prior art found:

- ☐ Foreign Patent(s)
- ☐ Non-Patent Literature
(journal articles, conference proceedings, new product announcements etc.)

➤ Relevant prior art **not found**:

- ☐ Results verified the lack of relevant prior art (helped determine patentability).
- ☐ Results were not useful in determining patentability or understanding the invention.

Comments:

Drop off or send completed forms to EIC1700 REMSEN 4B28



=> file reg

FILE 'REGISTRY' ENTERED AT 13:53:01 ON 15 NOV 2004
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Property values tagged with IC are from the ZIC/VINITI data file provided by InfoChem.

STRUCTURE FILE UPDATES: 14 NOV 2004 HIGHEST RN 780728-63-4
DICTIONARY FILE UPDATES: 14 NOV 2004 HIGHEST RN 780728-63-4

TSCA INFORMATION NOW CURRENT THROUGH MAY 21, 2004

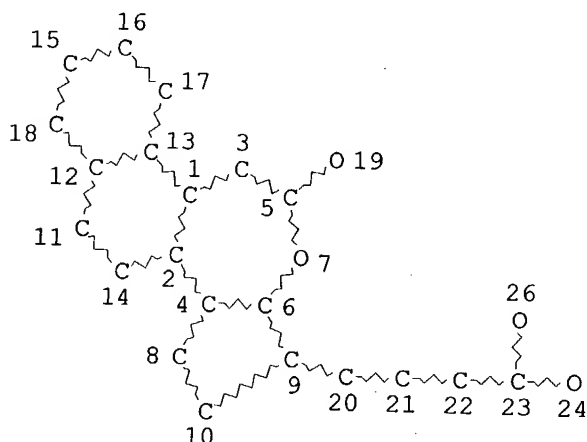
Please note that search-term pricing does apply when conducting SmartSELECT searches.

Crossover limits have been increased. See HELP CROSSOVER for details.

Experimental and calculated property data are now available. For more information enter HELP PROP at an arrow prompt in the file or refer to the file summary sheet on the web at:
<http://www.cas.org/ONLINE/DBSS/registryss.html>

=> d que

L10 STR



6 structures from the query

NODE ATTRIBUTES:
DEFAULT MLEVEL IS ATOM
DEFAULT ECLEVEL IS LIMITED

GRAPH ATTRIBUTES:
RING(S) ARE ISOLATED OR EMBEDDED
NUMBER OF NODES IS 25

STEREO ATTRIBUTES: NONE
L12 6 SEA FILE=REGISTRY SSS FUL L10

=> d l12 1-6

L12 ANSWER 1 OF 6 REGISTRY COPYRIGHT 2004 ACS on STN

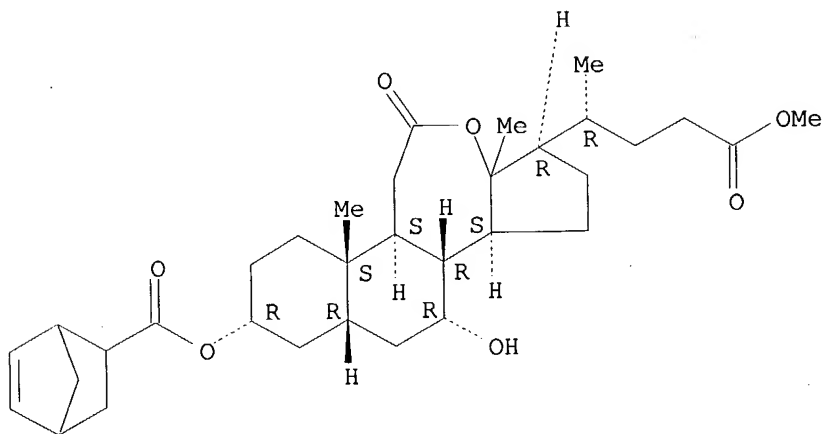
KATHLEEN FULLER EIC 1700 REMSEN 4B28 571/272-2505

RN 683786-04-1 REGISTRY
 CN 2H-Cyclopenta[b]naphth[2,1-d]oxepin-8-butanoic acid, 3-
 [(bicyclo[2.2.1]hept-5-en-2-ylcarbonyl)oxy]hexadecahydro-11-hydroxy-
 γ,4a,7a-trimethyl-, methyl ester, (γR,2R,4aS,4bS,8R,10aS,10bR,
 11R,12aR)-, polymer with 2,5-furandione (9CI) (CA INDEX NAME)
 FS STEREOSEARCH
 MF (C33 H48 O7 . C4 H2 O3)x
 CI PMS
 PCT Polyester, Polyester formed, Polyvinyl
 SR CA
 LC STN Files: CA, CAPLUS
 DT.CA Caplus document type: Journal
 RL.NP Roles from non-patents: FORM (Formation, nonpreparative)

CM 1

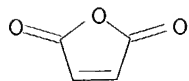
CRN 683786-02-9
 CMF C33 H48 O7

Absolute stereochemistry.



CM 2

CRN 108-31-6
 CMF C4 H2 O3



1 REFERENCES IN FILE CA (1907 TO DATE)
 1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

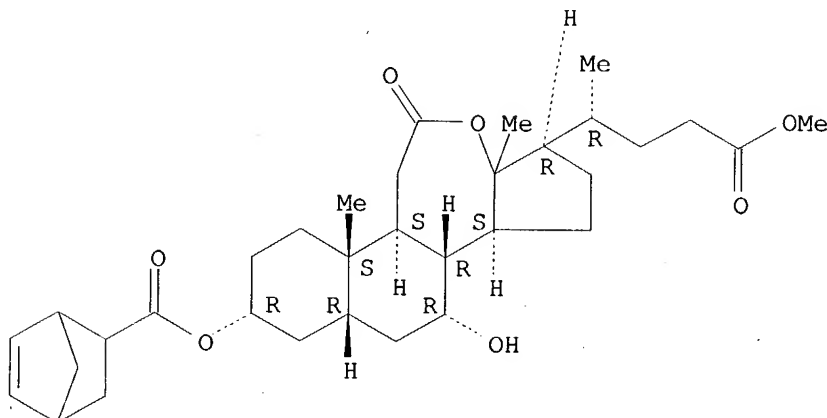
L12 ANSWER 2 OF 6 REGISTRY COPYRIGHT 2004 ACS on STN
 RN 683786-03-0 REGISTRY
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 [(bicyclo[2.2.1]hept-5-en-2-ylcarbonyl)oxy]hexadecahydro-γ,4a,7a-
 trimethyl-6-oxo-, methyl ester, (γR,2R,4aS,4bS,8R,10aS,10bR,12aR)-,
 polymer with 2,5-furandione (9CI) (CA INDEX NAME)

LC STN Files: CA, CAPLUS

DT.CA Caplus document type: Journal

RL.NP Roles from non-patents: PREP (Preparation); RACT (Reactant or reagent)

Absolute stereochemistry.



PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

1 REFERENCES IN FILE CA (1907 TO DATE)

1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

L12 ANSWER 4 OF 6 REGISTRY COPYRIGHT 2004 ACS on STN

RN 683786-01-8 REGISTRY

CN 2H-Cyclopenta[b]naphth[2,1-d]oxepin-8-butanoic acid, 2-
[(bicyclo[2.2.1]hept-5-en-2-ylcarbonyl)oxy]hexadecahydro- γ ,4a,7a-
trimethyl-6-oxo-, methyl ester, (γ R,2R,4aS,4bS,8R,10aS,10bR,12aR)-
(9CI) (CA INDEX NAME)

FS STEREOSEARCH

MF C33 H48 O6

CI COM

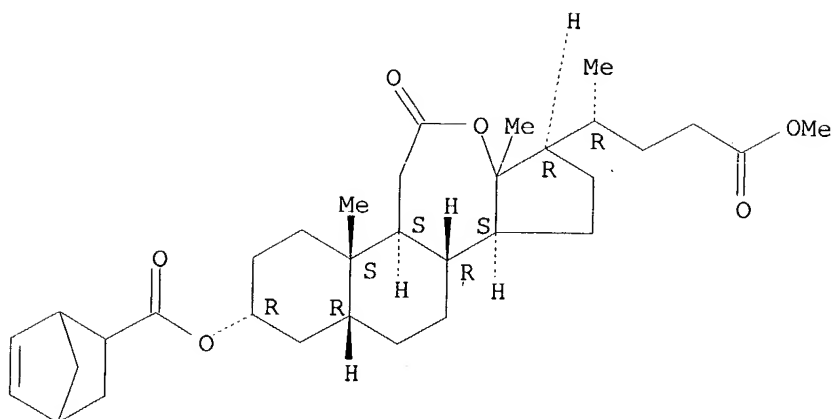
SR CA

LC STN Files: CA, CAPLUS

DT.CA Caplus document type: Journal

RL.NP Roles from non-patents: PREP (Preparation); RACT (Reactant or reagent)

Absolute stereochemistry.

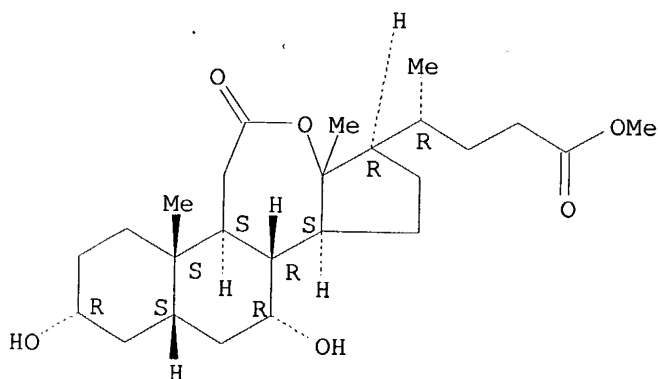


PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

L12 ANSWER 5 OF 6 REGISTRY COPYRIGHT 2004 ACS on STN
RN 683270-39-5 REGISTRY
CN 1H-Cyclopenta[b]naphth[2,1-d]oxepin-8-butanoic acid, hexadecahydro-2,11-dihydroxy- γ ,4a,7a-trimethyl-6-oxo-, methyl ester, (γ R,2R,4aS,4bS,8R,10aS,10bR,11R,12aS)- (9CI) (CA INDEX NAME)
FS STEREOSEARCH
MF C25 H40 O6
SR CA
LC STN Files: CA, CAPLUS
DT.CA Caplus document type: Journal
RL.NP Roles from non-patents: PREP (Preparation); RACT (Reactant or reagent)

Absolute stereochemistry.



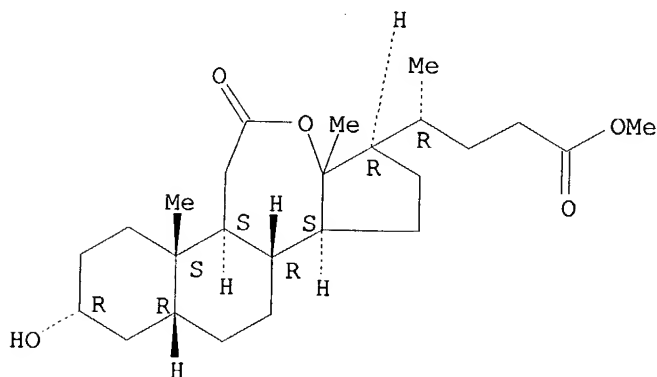
PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

KATHLEEN FULLER EIC 1700 REMSEN 4B28 571/272-2505

L12 ANSWER 6 OF 6 REGISTRY COPYRIGHT 2004 ACS on STN
RN 683270-37-3 REGISTRY
CN 1H-Cyclopenta[b]naphth[2,1-d]oxepin-8-butanoic acid, hexadecahydro-2-hydroxy- γ ,4a,7a-trimethyl-6-oxo-, methyl ester, (γ R,2R,4aS,4bS,8R,10aS,10bR,12aR)- (9CI) (CA INDEX NAME)
FS STEREOSEARCH
MF C25 H40 O5
SR CA
LC STN Files: CA, CAPLUS
DT.CA Caplus document type: Journal
RL.NP Roles from non-patents: PREP (Preparation); RACT (Reactant or reagent)

Absolute stereochemistry.



PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

=> file hcaplu

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FILE COVERS 1907 - 15 Nov 2004 VOL 141 ISS 21
FILE LAST UPDATED: 14 Nov 2004 (20041114/ED)

This file contains CAS Registry Numbers for easy and accurate

KATHLEEN FULLER EIC 1700 REMSEN 4B28 571/272-2505

substance identification.

=> s 112

L13

1 L12

1 CA reference from the sip structures

=> d 113 bib abs ind hitstr

applicant

L13 ANSWER 1 OF 1 HCAPLUS COPYRIGHT 2004 ACS on STN
 AN 2003:570079 HCAPLUS
 DN 140:383006
 TI Nonshrinkable photoresists for ArF lithography
 AU Kim, Jin-Baek; Oh, Tae Hwan; Choi, Jae-Hak; Lee, Jae-Jun
 CS Department of Chemistry, School of Molecular Science(BK21) and Center for
 Advanced Functional Polymers, Korea Advanced Institute of Science and
 Technology, Daejeon, 305-701, S. Korea
 SO Proceedings of SPIE-The International Society for Optical Engineering
 (2003), 5039(Pt. 2, Advances in Resist Technology and Processing XX),
 689-697 *June 2003 (Publication Date) 2-24-03 (Conference Date)*
 CODEN: PSISDG; ISSN: 0277-786X
 PB SPIE-The International Society for Optical Engineering
 DT Journal
 LA English
 AB Outgassing from the resist causes volume shrinkage of the resist film and
 extensive damage to optical lenses of exposure tools. Image distortion
 and throughput loss can take place due to the outgassing. In this study,
 the authors designed and synthesized a new acid labile group,
 7,7-dimethyloxepan-2-one, which was introduced into the matrix polymers
 for ArF chemical amplified resists. The 7,7-dimethyloxepan-2-one group was
 readily cleaved and the carboxylic acid functionality was formed by
 acid-catalyzed ring-opening reaction in the exposed region after
 post-exposure bake. The resist patterns of 0.22 μ m feature size were
 obtained with a conventional developer using an ArF exposure tool.
 CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other
 Reprographic Processes)
 ST nonshrinkable chem amplified photoresist vacuum UV polymer
 dimethyloxepanone group
 IT Ring opening
 (mechanism of acid-catalyzed cleavage of dimethyloxepanone
 groups-containing compds. in relation to vacuum-UV photoresists
 formulations)
 IT Photoresists
 (vacuum-UV, chemical amplified; nonshrinkable chemical amplified
 photoresists
 for ArF lithog. based on maleic anhydride copolymer with monomer containing
 dimethyloxepanone acid labile group)
 IT 75-59-2, Tetramethylammonium hydroxide
 RL: NUU (Other use, unclassified); USES (Uses)
 (developer; nonshrinkable chemical amplified photoresists for ArF lithog.
 based on maleic anhydride copolymer with monomer containing
 dimethyloxepanone acid labile group)
 IT 76638-13-6
 RL: CPS (Chemical process); PEP (Physical, engineering or chemical
 process); RCT (Reactant); PROC (Process); RACT (Reactant or reagent)
 (model compound; mechanism of acid-catalyzed cleavage of
 dimethyloxepanone groups in relation to vacuum-UV photoresists
 formulations)
 IT 1126-91-6P
 RL: CPS (Chemical process); PEP (Physical, engineering or chemical

*can't
be
102(a)
ref
nor
102(b)
nor
102(c)
ref.*

process); RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); PROC (Process); RACT (Reactant or reagent)
(model compound; mechanism of acid-catalyzed cleavage of dimethyloxepanone groups in relation to vacuum-UV photoresists formulations)

IT 683786-01-8P 683786-02-9P

RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT (Reactant or reagent)
(monomer; preparation of polymers with acid labile group, 7,7-dimethyloxepan-2-one groups for vacuum-UV photoresists formulations)

IT 683786-04-1

RL: FMU (Formation, unclassified); FORM (Formation, nonpreparative)
(nonshrinkable chemical amplified photoresists for ArF lithog. based on copolymers containing dimethyloxepanone acid labile group)

IT 683786-03-0P

RL: PRP (Properties); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(nonshrinkable chemical amplified photoresists for ArF lithog. based on copolymers containing dimethyloxepanone acid labile group)

IT 66003-78-9, Triphenylsulfonium triflate

RL: NUU (Other use, unclassified); USES (Uses)
(photoacid generator; nonshrinkable chemical amplified photoresists for ArF lithog. based on maleic anhydride copolymer with monomer containing dimethyloxepanone acid labile group)

IT 10538-64-4 28050-47-7

RL: RCT (Reactant); RACT (Reactant or reagent)
(reaction with chloroperoxybenzoic acid)

IT 683270-37-3P 683270-39-5P

RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT (Reactant or reagent)
(synthesis of monomer containing 7,7-dimethyloxepan-2-one acid labile group)

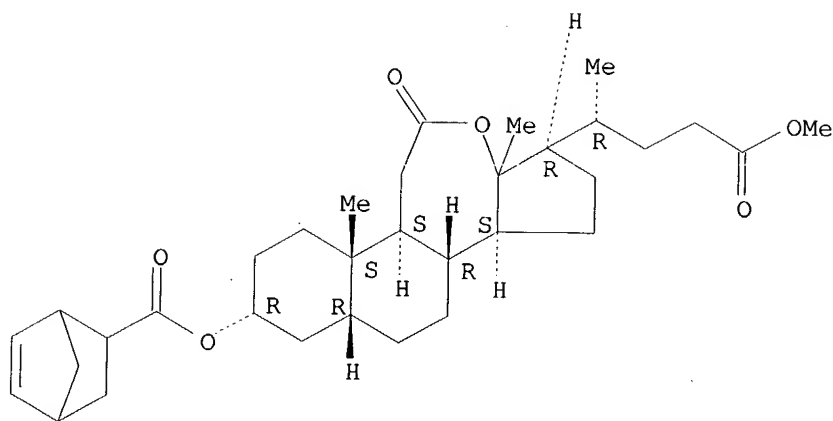
IT 683786-01-8P 683786-02-9P

RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT (Reactant or reagent)
(monomer; preparation of polymers with acid labile group, 7,7-dimethyloxepan-2-one groups for vacuum-UV photoresists formulations)

RN 683786-01-8 HCAPLUS

CN 2H-Cyclopenta[b]naphth[2,1-d]oxepin-8-butanoic acid, 2-
[(bicyclo[2.2.1]hept-5-en-2-ylcarbonyl)oxy]hexadecahydro- γ ,4a,7a-trimethyl-6-oxo-, methyl ester, (γ R,2R,4aS,4bS,8R,10aS,10bR,12aR)-(9CI) (CA INDEX NAME)

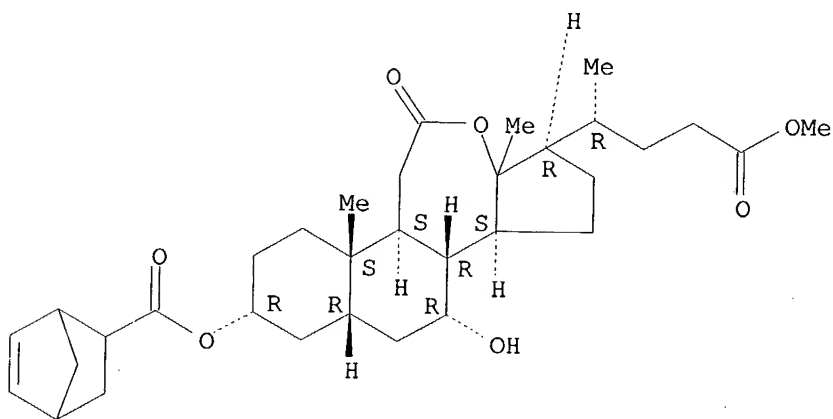
Absolute stereochemistry.



RN 683786-02-9 HCAPLUS

CN 2H-Cyclopenta[b]naphth[2,1-d]oxepin-8-butanoic acid, 2-
[(bicyclo[2.2.1]hept-5-en-2-ylcarbonyl)oxy]hexadecahydro-11-hydroxy-
γ,4a,7a-trimethyl-6-oxo-, methyl ester,
(γR,2R,4aS,4bS,8R,10aS,10bR,11R,12aR)- (9CI) (CA INDEX NAME)

Absolute stereochemistry.



IT 683786-04-1

RL: FMU (Formation, unclassified); FORM (Formation, nonpreparative)
(nonshrinkable chemical amplified photoresists for ArF lithog. based on
copolymers containing dimethyloxepanone acid labile group)

RN 683786-04-1 HCAPLUS

CN 2H-Cyclopenta[b]naphth[2,1-d]oxepin-8-butanoic acid, 3-
[(bicyclo[2.2.1]hept-5-en-2-ylcarbonyl)oxy]hexadecahydro-11-hydroxy-
γ,4a,7a-trimethyl-, methyl ester, (γR,2R,4aS,4bS,8R,10aS,10bR,
11R,12aR)-, polymer with 2,5-furandione (9CI) (CA INDEX NAME)

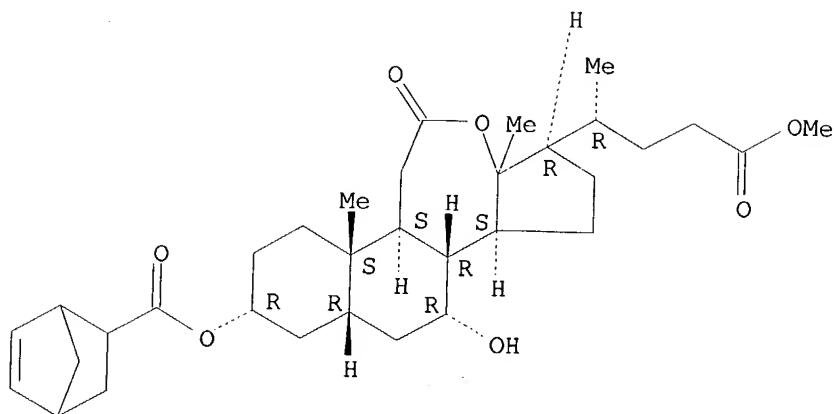
CM 1

CRN 683786-02-9

CMF C33 H48 O7

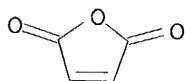
Absolute stereochemistry.

KATHLEEN FULLER EIC 1700 REMSEN 4B28 571/272-2505



CM 2

CRN 108-31-6
CMF C4 H2 O3



IT **683786-03-0P**

RL: PRP (Properties); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(nonshrinkable chemical amplified photoresists for ArF lithog. based on copolymers containing dimethyloxepanone acid labile group)

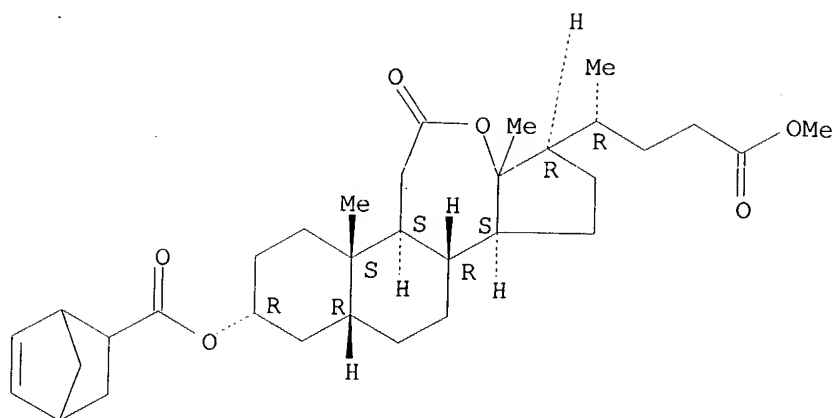
RN 683786-03-0 HCAPLUS

CN 2H-Cyclopenta[b]naphth[2,1-d]oxepin-8-butanoic acid, 2-
[(bicyclo[2.2.1]hept-5-en-2-ylcarbonyl)oxy]hexadecahydro-γ,4a,7a-
trimethyl-6-oxo-, methyl ester, (γR, 2R, 4aS, 4bS, 8R, 10aS, 10bR, 12aR)-,
polymer with 2,5-furandione (9CI) (CA INDEX NAME)

CM 1

CRN 683786-01-8
CMF C33 H48 O6

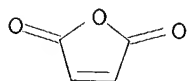
Absolute stereochemistry.



CM 2

CRN 108-31-6

CMF C4 H2 O3



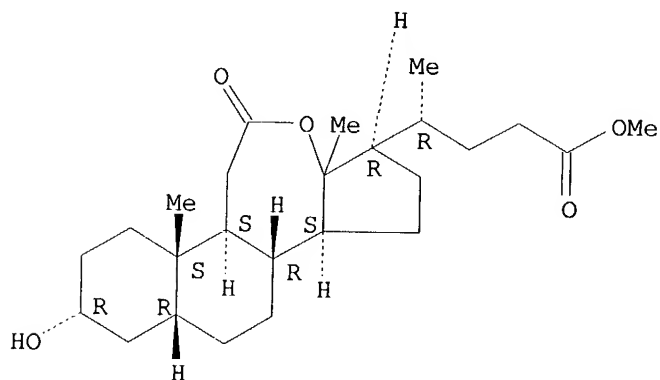
IT 683270-37-3P 683270-39-5P

RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT (Reactant or reagent)
(synthesis of monomer containing 7,7-dimethyloxepan-2-one acid labile group)

RN 683270-37-3 HCAPLUS

CN 1H-Cyclopenta[b]naphth[2,1-d]oxepin-8-butanoic acid, hexadecahydro-2-hydroxy- γ ,4a,7a-trimethyl-6-oxo-, methyl ester,
(γ R,2R,4aS,4bS,8R,10aS,10bR,12aR)- (9CI) (CA INDEX NAME)

Absolute stereochemistry.

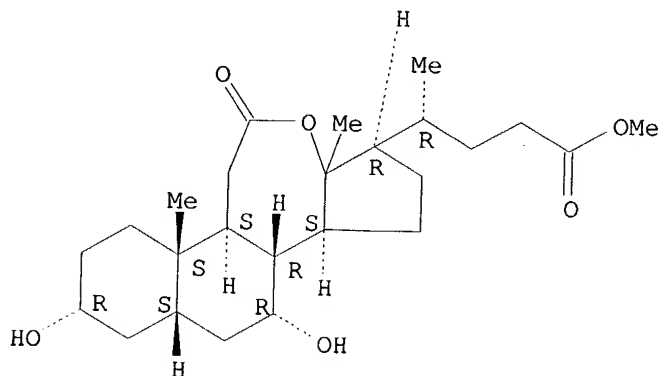


RN 683270-39-5 HCAPLUS

KATHLEEN FULLER EIC 1700 REMSEN 4B28 571/272-2505

CN 1H-Cyclopenta[b]naphth[2,1-d]oxepin-8-butanoic acid, hexadecahydro-2,11-dihydroxy- γ ,4a,7a-trimethyl-6-oxo-, methyl ester, (γ R,2R,4aS,4bS,8R,10aS,10bR,11R,12aS)- (9CI) (CA INDEX NAME)

Absolute stereochemistry.



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